ABSTRACT OF THE DISCLOSURE

A method for creating mask pattern data for
fabricating a circuit includes the steps of dividing
original mask pattern data into a plurality of regions
having a first size; performing OPC on the plurality of
regions and creating first mask pattern data based on the
plurality of processed regions; dividing the original mask
pattern data into a plurality of regions having a second
size; performing OPC on the plurality of regions and
creating second mask pattern data based on the plurality
of processed regions; and when non-matching data is present
as a result of matching comparison, setting the first or
second mask pattern data as the mask pattern data for
fabricating the circuit; and when non-matching data is
present as a result of the comparison, deleting the
non-matching data from the first or second mask pattern
data so as to create the mask pattern data for fabricating
the circuit.